

Session Title: [TD2] EUV Mask, Pellicle, Inspection 1

Session Date: November 15 (Tue.), 2022

Session Time: 11:20-12:40

Session Room: Room D (Sidney Room, 2F)

Session Chair: Prof. Sangsul Lee (POSTECH, Korea)

[TD2-1] [Invited] 11:20-11:50

Lensless EUV metrology for advanced lithography

Yasin Ekinci (Paul Scherrer Inst., Switzerland)

[TD2-2] [Invited] 11:50-12:20

**EUV Sources and Their Applications** 

Dong Gun Lee (ESOL Inc., Korea)

[TD2-3] 12:20-12:40

Guidance and Required Capability for EUV Pellicle Development and Production Jae Hyuck Choi (FST, Korea)